

# XP 002153004

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AP - JP19860159793 19860709

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DC - D17

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PA - (HGET ) HIGETA SHOYU KK

PN - JP63017901 A 19880125 DW198809 004pp

PR - JP19860159793 19860709

XA - C1988-027675

XIC - C08B-037/08

AB - J63017901 Purifying chitosan comprises adjusting the pH of a soln. contg. chitosan to at least 6.0, pref. 6.5 to form deposit. The deposit is, if necessary, washed with water and dissolved in an acid. The pH of the obtd. soln. is adjusted to at least 6.0, pref. at least 6.5. These procedures of washing, dissolution and deposition are pref. repeated.

- ADVANTAGE - Deposition of chitosan is completely effected by only adjusting the pH of a soln. contg. chitosan. The deposit can be sepd. easily by filtration.(0/1)

IW - PURIFICATION CHITOSAN ADJUST PH SOLUTION CONTAIN CHITOSAN FORM DEPOSIT  
OPTION WASHING WATER DISSOLVE ACID

IKW - PURIFICATION CHITOSAN ADJUST PH SOLUTION CONTAIN CHITOSAN FORM DEPOSIT  
OPTION WASHING WATER DISSOLVE ACID

NC - 001

OPD - 1986-07-09

ORD - 1988-01-25

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TI - Purificn. of chitosan - by adjusting pH of soln. contg. chitosan, to about 6, to form deposit which is opt. washed with water and dissolved in acid

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